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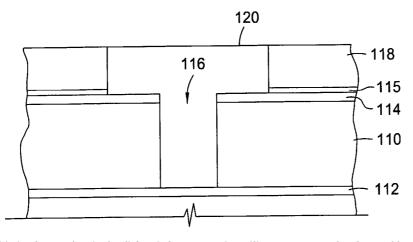
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For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: METHOD OF IMPROVING INTERLAYER ADHESION



(57) Abstract: Methods provided for processing depositing substrate for adhesion layer having a low dielectric constant between two low k dielectric layers. In one aspect, the invention provides a method for processing a substrate including depositing a barrier layer (112) on the substrate, wherein the barrier laver comprises silicon and carbon and has a dielectric constant less than 4, depositing a dielectric initiation layer adjacent the barrier layer, and depositing a first dielectric layer (110) adjacent the dielectric

initiation layer, wherein the dielectric layer comprises silicon, oxygen, and carbon and has a dielectric constant of about 3 or less.

Inti nal Application No PCT/US2004/006849

A. CLASSIFICATION OF SUBJECT MATTER
IPC 7 H01L21/31 H01L21/768 C23C16/40 C23C16/32 According to International Patent Classification (IPC) or to both national classification and IPC $\begin{array}{ll} \mbox{Minimum documentation searched (classification system followed by classification symbols)} \\ \mbox{IPC 7} & \mbox{H01L} & \mbox{C23C} \end{array}$ Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched Electronic data base consulted during the international search (name of data base and, where practical, search terms used) EPO-Internal, WPI Data, PAJ, IBM-TDB C. DOCUMENTS CONSIDERED TO BE RELEVANT Citation of document, with indication, where appropriate, of the relevant passages Relevant to claim No. Category US 2003/003765 A1 (LYTLE STEVEN ALAN ET AL) 2 January 2003 (2003-01-02) 1,11, 14-17,20 Χ page 2, paragraph 23 page 3, paragraphs 26,27 figure 2 2-8,12, Α US 6 340 435 B1 (CHAPRA NASREEN GAZALA ET 14-17,20 χ AL) 22 January 2002 (2002-01-22) column 5, line 46 - column 6, line 26 column 9, line 44 - column 11, line 3 column 11, lines 46-51 Α 1-8, 11-13 -/-- χ Further documents are listed in the continuation of box C. Patent family members are listed in annex. ° Special categories of cited documents: "T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the "A" document defining the general state of the art which is not considered to be of particular relevance invention "E" earlier document but published on or after the international "X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone filing date "L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified) "Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such docu-"O" document referring to an oral disclosure, use, exhibition or ments, such combination being obvious to a person skilled in the art. "P" document published prior to the international filing date but later than the priority date claimed "&" document member of the same patent family Date of the actual completion of the international search Date of mailing of the international search report **19**. 01. 2005 1 October 2004 Name and mailing address of the ISA Authorized officer European Patent Office, P.B. 5818 Patentlaan 2 NL - 2280 HV Rijswijk Tel. (+31-70) 340-2040, Tx. 31 651 epo nl, Fax: (+31-70) 340-3016 Ekoué, A

Inte....al Application No PCT/US2004/006849

Category °	ation) DOCUMENTS CONSIDERED TO BE RELEVANT Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
Jalegury	onduction document, with indication, where appropriate, or the relevant passages	Helevant to Claim No.
X	US 6 054 379 A (JENG SHIN-PUU ET AL) 25 April 2000 (2000-04-25) column 10, line 18 - column 11, line 43 column 14, lines 20-23	1,20
		2-8, 11-18
	US 6 521 300 B1 (HUANG CHIH-AN ET AL) 18 February 2003 (2003-02-18) column 3, line 23 - column 4, line 26	1-8, 11-18,20
	,	

International application No. PCT/US2004/006849

INTERNATIONAL SEARCH REPORT

Box II	Observations where certain claims were found unsearchable (Continuation of item 2 of first sheet)
This Inter	national Search Report has not been established in respect of certain claims under Article 17(2)(a) for the following reasons:
	Claims Nos.: secause they relate to subject matter not required to be searched by this Authority, namely:
'	Claims Nos.: because they relate to parts of the International Application that do not comply with the prescribed requirements to such an extent that no meaningful International Search can be carried out, specifically:
b	Claims Nos.: lecause they are dependent claims and are not drafted in accordance with the second and third sentences of Rule 6.4(a).
Box III C	Observations where unity of invention is lacking (Continuation of Item 3 of first sheet)
This Intern	ational Searching Authority found multiple inventions in this international application, as follows:
\$	see additional sheet
1. A	s all required additional search fees were timely paid by the applicant, this International Search Report covers all earchable claims.
2. As	s all searchable claims could be searched without effort justifying an additional fee, this Authority did not invite payment any additional fee.
3. As	s only some of the required additional search fees were timely paid by the applicant, this International Search Report overs only those claims for which fees were paid, specifically claims Nos.:
	o required additional search fees were timely paid by the applicant. Consequently, this International Search Report is stricted to the invention first mentioned in the claims; it is covered by claims Nos.: - 8, 11 - 18, 20
Remark on	Protest The additional search fees were accompanied by the applicant's protest. No protest accompanied the payment of additional search fees.

FURTHER INFORMATION CONTINUED FROM PCT/ISA/ 210

This International Searching Authority found multiple (groups of) inventions in this international application, as follows:

1. claims: 1-8, 11-18, 20

Method for processing a substrate comprising a dielectric initiation layer between two low-k dielectric layers wherein the dielectric layer is deposited by introducing a processing gas comprising an organosilicon compound, a carbon-containing oxidizing compound, and a nitrating compound into a processing chamber, and reacting the processing gas to deposit the dielectric initiation layer.

2. claims: 9, 10, 19, 21-23

Method for processing a substrate comprising a dielectric initiation layer between two low-k dielectric layers wherein the dielectric layer(s) is/are cured using an e-beam technique or exposed to a nitrogen-free oxidizing plasma prior to subsequent processing.

Information on patent family members

In Il Application No PCT/US2004/006849

Patent document cited in search report		Publication date		Patent family member(s)		Publication date
US 2003003765	A1	02-01-2003	GB JP US	2387027 2003243505 2003001273	Α	01-10-2003 29-08-2003 02-01-2003
US 6340435	B1	22-01-2002	$\begin{array}{cccccccccccccccccccccccccccccccccccc$	2002014545 2002045361 1055012 2002503879 408369 9941423 2001004479 2003064610 2001005546 2003124859 2003162410 6593247 6660663	A AA B AAABAAA T B AAAAAABBBBBBBBBAAABBBBBBBB	11-09-2001 25-04-2000 13-12-2000 20-04-2001 21-01-2002 20-06-2002 04-07-2002 23-10-2003 31-12-2002 07-02-2002 18-04-2002 29-11-2000 05-02-2002 11-10-2000 19-08-1999 21-06-2001 03-04-2003 28-06-2001 03-07-2003 28-08-2003 15-07-2003 25-03-2003 13-05-2003 12-02-2004 29-04-2004 29-04-2004 26-02-2004 30-09-2003 26-08-2004 22-07-2003 06-06-2000 19-06-2003 02-07-2002 28-01-2003 03-01-2002 29-07-2004 14-10-2004 15-08-2002
US 6054379	Α	25-04-2000	EP JP TW US US US US US US US US US US US	1055012 / 2002503879 / 408369 / 2002074309 / 2002084257 / 9941423 / 6287990 / 2001004479 / 2003064610 / 2001005546 / 2003113992 / 6340435 / 20025038790 / 2003064610 / 2003064610 / 2003064610 / 2003064610 / 2003113992 / 6340435 / 2003113992 / 6340435 / 2003113992 / 6340435 / 2003113992 / 6340435 / 2003113992 / 6340435 / 2003113992 / 200311000000000000000000000000000000000	T B A1 A1 A2 A B1 A1 A1 A1	29-11-2000 05-02-2002 11-10-2000 20-06-2002 04-07-2002 19-08-1999 06-06-2000 11-09-2001 21-06-2001 03-04-2003 28-06-2001 19-06-2003 22-01-2002

Information on patent family members

Intnal Application No PCT/US2004/006849

Patent document cited in search report	Publication date		Patent family member(s)	Publication date
US 6054379 A		US	6413583 B1	02-07-2002
		US	6511909 B1	28-01-2003
		US	2003162410 A1	28-08-2003
		US	6511903 B1	28-01-2003
		US	2002000670 A1	03-01-2002
		US	6593247 B1	15-07-2003
		US	6660663 B1	09-12-2003
		US	6537929 B1	25-03-2003
		US	6562690 B1	13-05-2003
		US	6541282 B1	01-04-2003
		US	2004029400 A1	12-02-2004
		US	2004082199 A1	29-04-2004
		US	2004038545 A1	26-02-2004
		US	6627532 B1	30-09-2003
		US	2004147109 A1	29-07-2004
		บร	2004166665 A1	26-08-2004
		US	2004201103 A1	14-10-2004
		US	2002045361 A1	18-04-2002
		US	6596655 B1	22-07-2003
		US 	2002111042 A1	15-08-2002
US 6521300 B1	20-02-2003	US	2003035904 A1	20-02-2003